

Photomask Blank

ABSTRACT

5 A photomask blank has on a transparent substrate, an optional first film, a second
film, a third film, and a fourth film. The first and third films are formed of silicon-
containing materials which are resistant to chlorine base dry etching and removable by
fluorine base dry etching. The second and fourth films are formed of chromium-
10 containing materials which are resistant to fluorine base dry etching and removable by
chlorine base dry etching. An etching clear time of the fourth film is longer than an
etching clear time of the second film on chlorine base dry etching.

Fig. 1A